

**REMARKS**

Claims 1-9 remain pending in the above-identified application. Claims 1 and 4 are amended. No claims are canceled or added. The specification is amended in view of an informality.

Applicants appreciate the courtesy extended by the Examiner in granting and conducting the December 18, 2003 telephone interview. Applicants summarize the interview discussion as follows:

Applicants' representative began the discussion by identifying in the claims the depositing, heat treating (or silicide applying), and removing steps and their repetition. He referred to this process in an abbreviated format as step 1; step 2; step 3; step 1; step 2; and step 3. He then referenced the arguments made of record via the July 25, 2003 Preliminary Amendment as follows:

The claim rejection relies on *Wieczorek et al.* (U.S. Patent No. 6,207,563) and a publication of Wolf et al. (*Wolf*). Applicants' representative initially explained that *Wieczorek et al.* (without reference to *Wolf*) teaches two embodiments. The process of the first embodiment can be represented as step 1; step 2; step 3; step 2, and the process of the second embodiment can be represented as step 1; step 1; step 2; step 3; step 2. In particular, *Wieczorek et al.* does not teach repeating the removing step as claimed.

Applicants' representative also explained that the present anticipation rejection could not properly rely on both *Wieczorek et al.* and *Wolf*, because *Wieczorek et al.* does not really incorporate *Wolf* by reference. Nonetheless, the interview continued, because an obviousness rejection may rely on two references, so, for compact prosecution, applicants' representative explained why the two references would not support an obviousness rejection either.

Applicants' representative asked the Examiner where he thought *Wolf* disclosed repeating the removing step. Applicants' representative now respectfully reports that the Examiner did not provide a clear answer. Instead, he read portions of pages 150<sup>1</sup> and 152. These portions included "... makes it possible to remove ..." in the bottom paragraph of page 150 and "... is etched away ..." in paragraph 4 on the bottom of page 151. The Examiner represented these excerpts as a disclosure of a repetition of a removing step.<sup>2</sup>

Also during the interview, the Examiner, without firmly committing, noted the following subject matter that did not initially seem to him as either anticipated or rendered obvious by *Wieczorek et al.* and *Wolf*:

The Examiner referenced page 7, lines 27-28, and page 8, lines 11-13, which discloses that a C54 phase, low resistance, titanium silicide film is formed. He suggested that applicants consider adding a recitation like "to form a C54 phase, low resistance, titanium silicide film" at the end of independent claims 1 and 4.

Applicants appreciate the suggestion and amend the claims as shown above. That is, claims 1 and 4 are amended in accordance with the Examiner's suggestions. Support for the amendment can be found on page 7, lines 27-28, and on page 8, lines 11-13, of the application.

Applicants now request the withdrawal of the art rejection for at least the following reason:

Independent claims 1 and 4 both describe a method that includes forming a C54 phase titanium silicide film by repeating a sequence of a depositing step, a heat treating step (or silicide

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<sup>1</sup> Although the Examiner wrote in the Office Action that the rejection relies on page "140" of *Wolf*, he indicated during the interview that he meant instead that the rejection relies on page "150."

<sup>2</sup> Applicants respond that the quoted text from page 150 is a description of characteristics of a process, and the quoted text from page 151 is an unrepeated removing step. Applicants respectfully disagree that the teachings of *Wieczorek et al.* and *Wolf* can be properly combined to render the claims obvious.

applying step), and a removing step once or a number of times. The remaining claims depend from either claim 1 or claim 4, so, by virtue of their dependency, they also describe a method that includes the referenced step.

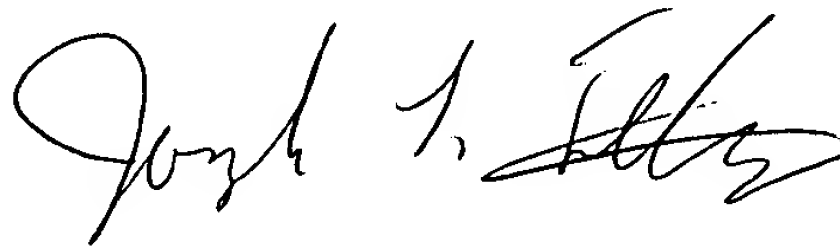
Applicants submit that neither *Wieczorek et al.* nor *Wolf* teach or suggest a method that includes the referenced step. *Wieczorek et al.* does not disclose forming a C54 phase titanium silicide film by performing as described in the claims. *Wolf* also does not disclose such a method. *Wolf* only discloses depositing a thin layer of Ti and W on the  $\text{TiSi}_2$  for preventing the formation of the high-resistivity  $\text{TiF}_3$  layer on the  $\text{TiSi}_2$  during the CVD W process. Accordingly, the pending claims distinguish over the *Wieczorek et al.* and *Wolf* disclosures.

For at least the reasons provided above, applicants now solicit the withdrawal of the art rejection of claims 1-9.

In view of the amendments and remarks above, applicants now submit that the application is in condition for allowance. Accordingly, a Notice of Allowability is hereby requested. If for any reason it is felt that this application is not now in condition for allowance, the Examiner is invited to contact applicants' undersigned attorney at the telephone number indicated below to arrange for disposition of this case.

In the event that this paper is not timely filed, applicants petition for an appropriate extension of time. The fees for such an extension, or any other fees which may be due, may be charged to Deposit Account No. 50-2866.

Respectfully submitted,  
WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP

A handwritten signature in black ink, appearing to read "Joseph L. Felber". The signature is fluid and cursive, with the first name "Joseph" being more legible than the last name "Felber".

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